

R&D for pixel detectors in the future hadron colliders

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GDR intensity frontier Retour d'expérience et futurs projets 19 septembre 2023

- Introduction: FCC timeline
- Requirements for future trackers
- Pixel front-end time resolution
- Technology used in current CERN experiments
- Technologies under consideration
- CPPM activities
- Conclusion

Introduction

- Realistic schedule takes into account the past experience in building colliders at CERN
- The future collider at CERN cannot start physics operation before ~ 2045 but construction will proceed in parallel to the HL-LHC operation
- The operation of the FCC-hh is planned for 2070
- It is obviously not possible to define now the technology of the **pixel detectors** for the FCC-hh
	- \blacksquare This technology does not yet exist
- Which "long-term R&D" is essential now to enable the technical design of experiments in 30 years ?

Realistic schedule

Pixel detectors requirements in the future experiments

- **EXECT:** Future Circular Collider tracker (FCC-hh)
- **Efficient reconstruction of charged particle tracks in an** environment of high pileup density (1000 pileup)
	- Position: $7.5 9.5 \mu m$, Time resolution = 5 ps
	- Radiation levels: 40 Grad and 1×10^{18} neq/cm2
		- $-$ 40 times more intense than the HL-LHC.
	- Huge data rates
		- $-$ Hit rate of 30 GHz/cm² (HL-LHC \times 10)
		- ━ Need of 50-100 Gbps data links (low power, low material)
	- A big challenge in sensor and ASIC design

Intermediate steps :

- The ATLAS and CMS tracker upgrades
	- ━ The two innermost pixel layers will need to be replaced after 5 years
	- ━ The pixel time resolution of 50 ps is needed to boost the ATLAS performance
- **Electron Ion Collider (EIC)**
	- ━ New accelerator to be built at Brookhaven National Laboratory will start operating In 2031
	- ━ 4D detectors based on AC-LGADs are envisioned to provide timing capability
	- Time resolution of 30 ps is required
	- Spatial resolutions of 15 μ m to 150 μ m depending on the location.
- **Electron colliders**
	- Linear colliders (ILC, CLIC) and Circular colliders (FCC-ee)
	- High precision is required for physics measurements
	- Pixel size in the vertex detector < $25 \mu m \times 25 \mu m$
	- Time resolution at the ns level is required
	- Potential applications of precision timing at the ps level under investigation

Time resolution of the pixel FE

σ *jitter*

- Due to the noise of the electronic front-end including the sensor
	- \blacksquare The jitter is proportional to the rise time (\sim 1/BW) and inversely proportional to the S/N ratio.

$\sigma_{timewalk}$

- Related to the variation of the deposited charge eventby-event
	- ━ Variation of the time of arrival (TOA)
	- ━ Correct the time of arrival (TOA) with a calibration based on the time over the threshold (TOT)

σ_{Landau}

- Due to the Landau distribution of the deposited charge
	- ━ The spatial variation along the path and charges from different depths are collected at different times.
	- The effect is small for thinner sensor, Absent in 3D detectors but not negligible in LGAD sensors

 σ_{TDC}

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Technology used in current CERN experiments

- The CERN community is lagging behind in the use of the new processes
	- ━ Accessibility and cost
- \triangleright Risk of technology aging and foundry can abandon the node
- Most of the designs for CERN experiments are based on 65 nm and 130nm CMOS
	- ━ Technologies are already fifteentwenty years old
- The 28nm CMOS process is considered as the next node for highly integrated chips such as pixel readout chips
- The requirements of electron and heavyion colliders seem to be mostly within reach of technologies from HL-LHC
- Within the next 20 years, it is certainly possible that we will have access to the most advanced CMOS nodes available today

Technologies under consideration

- For ASICs, the microelectronics industry has reached nanoscale CMOS nodes (< 3nm), based on new transistor structures (FinFETs and GAA)
- High-performance CMOS image sensors are based on stacked active layers to reduce pixel pitch and increase functionality
- 3D integration of a readout chip with a silicon photonics device may open way to high-rate data transmission (≥ 100 Gb/s)
- **Beyond CMOS:**
	- ━ Carbon nanotubes and graphene have generated much interest: not yet clear if they will be a replacement for Si CMOS
- CMOS nodes below 28nm need to be qualified
	- ━ Potential use in future applications requiring extreme miniaturization, High speed, and low power

Tolerance to high TID of nanoscale CMOS

- 16 nm Si FinFETs have the best TID tolerance
- 16 nm pFinFET : Short channel devices shows better TID tolerance
- In general, pMOS have the worst TID tolerance
- No existence of bad annealing for modes \leq 28 nm

Stefano Bonaldo presentation: CERN DRDT7.4 - 2023, March 15th

Timing sensors for high radiation levels

3D sensors LGAD sensors

- LGAD sensors under irradiation → Modification of the gain implant profile
- Not adapted for fluence > $2-3 \times 10^{15}$ neq/cm²

Fraction of gain still active versus neutron irradiation

M. Ferrero et. Al : Nuclear Inst. and Methods in Physics Research, A 919 (2019) 16–26

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- Developed and tested within the TimeSPOT project
- \blacksquare Pixels of 55 μ m pitch
- No performance loss up to fluences of 2.5×10^{16} neg/cm²

CPPM activities

R&D CPPM projects

- Transverse project : DÉPHY : DÉveloppements Pixels HYbrides et monolithiques radio-tolérants» \rightarrow Master Project IN2P3 that replaced the DICE project
- AIDAinnova Project (28nm + HVCMOS) accepted, started 2021
- CERN-DRD projects :
	- \rightarrow 4D and 5D techniques (WG 7.3) \rightarrow High-precision timing
	- \equiv Extreme environments (WG 7.4) \rightarrow Radiation hardness of advanced CMOS nodes
- RD53 collaboration started to be interested in 28 nm for the design of the pixel RO chip to be used for the replacement of the 2 internal ITK layers
- R&D axis around hybrid pixels (25µm× 25µm) with the 28nm node and Focuses on :
	- ━ The radiation tolerance of the technology
	- ━ Time measurement with a resolution better than 50ps
- Mini@sic of 2 mm x 1 mm submitted December 24-2022
- Different structures implemented :
	- ━ SET Testing structures
	- ━ Ring oscillators for the TID tolerance test
	- ━ Small pixel matrix: Fast charge amplifier
	- ━ Devices for TID tolerance test

SEE/SET Testing

- The SEE mitigation is a major challenge for the next generation of pixel chips because of the luminosity increase
- SET propagation through combinatorial logic and generate SEU in memories, FIFO and state machines
- SET sensitivity increases with process advance and with speed
- SET test structures implemented in the prototype chip will allow characterizing the 28nm CMOS process for SET tolerance
- Objectives :
	- ━ Measure the SET cross-section
	- **一** Measure the SET pulse width with a **good** resolution < 20 ps
	- ━ Measure the effect of the std cell size
- Allows for example to define the delay to be imposed for the triplication with time mitigation

SET Bloc design

Designer : Denis Fougeron

- **Each sub-bloc contains**
	- \rightarrow 3 target cells made up of thousands of basic cells + 1 calibration input
	- ━ Circuit for SET width measurement 96 delay cells (13ps/cell) -> from a few ps to 1 ns
	- </u> Shift register to send the data to the output when a trigger signal occurs
- 31 SFT sub blocs
	- \sim 24 uses SVT target cells (7T, 9T, 12T) \rightarrow Effect of the cell size
	- ━ 7 uses LVT or HVT target cells -> Effect of the device options
- The whole bloc contains 6 inputs / 13 outputs
- In addition to SET testing, this constitutes a sub-block of the TDC required in the pixel front end

Ring Oscillator Design

Designer : Eva Joly

- Study the effect of TID on the performances of digital standard cells
	- ━ Timing of combinatorial cells
	- Leakage currents and static power
- 96 ROsc sub-bloc
	- \equiv Cell size (7T, 9T, 12T) -> cell size effects
	- ━ Driving (D0, D2, D4) -> cell driving effects
	- ━ SVT, LVT, HVT -> device threshold effects
- Design based on the digital flow

Simulation

ROsc sub-bloc synoptic

Fast amplifier design

- Study the limits to time resolution in the analog front- end designed with the 28 nm CMOS process
- Effects of the Current bias, power supply, Bandwidth, Noise …
- Design and test a pixel array of 36 × 12 cells where only the analog part is considered and implemented
- Cf **HitOr** :Cs ,
Isensor **CSA** Comp

Analog FE pixel design

The time resolution of a detector:

 $\sigma_{total}^2 = \sigma_{jitter}^2 + \sigma_{timewalk}^2 + \sigma_{Landau}^2 + \sigma_{TDC}^2$

Minimizing the front-end jitter corresponds to :

- ━ Low RMS noise of the charge amplifier (CSA)
- ━ High output voltage
- \equiv Small rise time \rightarrow High bandwidth

Analog FE pixel prototype

- For each pixel :
	- The charge amplifier current bias can be set in the range of 2µA-20µA
	- MOM capacitance connected to each preamplifier input -> test for different input capacitance values
- Large bandwidth buffers (> 1 GHz) implemented and connected for a few pixels for direct jitter measurement
- Simulations for $I_{CSA} = 5 \mu A$
	- \rightarrow dV/dt = 100 mV/ns
	- RMS noise = 97 e- RMS for Cin = 100 fF
	- Jitter < 100 ps RMS for input charge > 4 ke-
	- Jitter < 40 ps RMS for charge > 10 ke-
- Each pixel contains : CSA + Discriminator + 6 bit DAC
	- $Size: 20 \mu m \times 12 \mu m$

50 superimposed transient noise simulations

Design progress

- The chip prototype submitted in December 2022
- Test set-up is under preparation
	- ━ Adaptation of the set-up based on the BB board
	- ━ Design and fabrication of chip test boards
- Functional tests (Q4-2023)
- Irradiation test (TID + SEE) Q1-2024
- The signing of 3-way 28nm NDA was finally done
	- ━ The CERN PDK will be used for future designs
- A new submission planned for Q3-2024
	- ━ Dedicated to pixel array performance improvement
	- ━ Plan to bump the readout chip with the sensor

Thank you for your attention Thank you for your attention

Front-end electronics and ASIC R&D

Charge amplifier (CSA) Vout = CF×Qsensor Slow slew rate Less noise

Transimpedance amplifier Low Rin Vout = RF×Isensor High bandwidth High noise

- **•** Front end based on charge amplifier (CSA)
- **■** High-resolution TDC
	- ━ 1 TDC can be shared by several FEs
- TOA and TOT measurements

1st stage collider, FCC-ee: electron-positron collisions 90-360 GeV Construction: 2033-2045 \rightarrow Physics operation: 2048-2063

2 nd stage collider, FCC-hh: proton-proton collisions at ≥ 100 TeV Construction: 2058-2070 \rightarrow Physics operation: ~ 2070-2095

Care should be taken when comparing to other proposed facilities, for which in some cases only the (optimistic) technical schedule is shown

The effects of timing

■ Timing layers (HL-LHC)

- ━ CMS and ATLAS are building silicon-based timing detector layers that will timestamp each track with a **precision of 30 ps**
- ━ ATLAS High Granularity Timing Detector (HGTD) and the CMS Timing Detector (MTD) placed in the forward regions $(2.4 < |n| < 4.0)$
- Based on novel Low Gain Avalanche Detectors (LGADs)
- ━ The readout chip HGTD is an array of 15×15 channels of 1.1 mm × 1.1 mm
- Designed with TSMC 130 nm CMOS process

■ 4D tracking

- ━ Timing information will be more important at future high-energy, high-luminosity hadron colliders with much higher levels of pileup
- 4D tracking: timing at each layer along the tracks

> At ultra-high doses, two dominating TID effects related to charge trapping in STI oxides:

1) Increase of OFF-leakage current

2) Loss of trasconductance (RINCE)

F. Faccio, et al., IEEE Trans. Nucl. Sci., 62(6), 2015; S. Bonaldo, et al. IEEE Trans. Nucl. Sci., 67(7), 2020

- Better gate control over the channel ٠
- Faster switching speed п
- More drive-current per footprint п
- Lower switching voltage п
- **No ELT solution** Đ,

Results on 16 nm bulk Si FinFET

- · Manufacturer: TSMC
- " Tested up to 1 Grad
- " Shallow trench Isolation (STI)
- Designed in different combination fin/finger

